In re application of:

Group Art Unit: 1732

Brian W. Baird, Michael J. Wolfe, Richard S. Harris, Kevin P. Fahey, Lian-Cheng Zou, and Thomas R. McNeil

Application No. 10/017,497

Filed: December 14, 2001

For: ULTRAVIOLET LASER ABLATIVE

PATTERNING OF MICROSTRUCTURES

IN SEMICONDUCTORS

Date: February 4, 2005

Examiner: Dr. Stefan Staicovici

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AMENDMENT A

TO THE COMMISSIONER FOR PATENTS:

In response to the October 4, 2004 Office action, please amend the above-identified application as follows.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims that begins on page 3 of this paper.

Remarks begin on page 12 of this paper.

02/10/2005 CCHAU1

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